



# Call for Papers – DPS 2021

42<sup>nd</sup> International Symposium on Dry Process

November 18(Thu) – 19(Fri), 2021

**ONLINE SYMPOSIUM**

**Paper Submission Deadline: July 16, 2021**

*Deadlines will be respected, hence early submission is encouraged.*

Author instructions and information about DPS can be found at:

<http://www.dry-process.org/2021/>



The 42nd International Symposium on Dry Process (DPS2021) will be held as an **ONLINE SYMPOSIUM** from November 18th to 19th, 2021. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than four decades.

**Theme:** Dry processes and related technologies from fundamentals to applications

**Topics:**

1. Etching Technologies
2. Manufacturing Technologies (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring Systems
5. Computational Approaches (Modeling, Simulation and Machine Learning) for Dry Process
6. Plasma Generation (Equipment/Source)
7. Deposition Technologies (CVD / PVD)
8. Atomic Layer Processes (ALD/ALE)
9. Plasma Processes for 3D Device, FPD, Photovoltaic Devices
10. Plasma Processes for New Material Devices (MRAM, Power, Organic)
11. Plasma Processes for Biological and Medical application, MEMS
12. Atmospheric Pressure Plasma and Liquid Plasma
13. New Dry Process Concepts

**Arranged session:**

- A1 – Applications and Researches of Atomic Layer Controlled Etching and Deposition (ALE/ALD/Area Selective-ALD)
- A2 – Challenges to Limits for High Aspect Ratio Etching
- A3 – Rethinking of Cryogenic Etching

For further general information, please contact: [e-mail:dps2021@officepolaris.co.jp](mailto:dps2021@officepolaris.co.jp)

Organizing Committee Chair: Hisataka Hayashi (KIOXIA Corporation)  
Executive Committee Chair: Takanobu Watanabe (Waseda University)  
Program Committee Chair: Takahiro Maruyama (Renesas Electronics Corp.)  
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**URL:** <http://www.dry-process.org/2021/>